PATENT Atty. Dkt. No. APPM/001570.C2/DSM/HDP/JP Serial No.: 08/912 112

IN THE CLAIMS:

Please amend the claims as follows:

1-14. (Canceled)

- 15. (Currently Amended) \underline{A} An electrically symmetric processing enclosure, comprising:
- a chamber body defining an annular interior processing region, the annular processing region tapering towards a lower end;
- an exhaust passage concentrically positioned in the lower end of the chamber body;
- a cantilever mounted annular substrate support member affixed to the chamber body at a position above and concentric to the exhaust passage; and
- a lid member disposed over an annular open top portion of the chamber body, the lid member having an energy transmitting dome made of a dielectric material, an energy delivery assembly, and a temperature control assembly mounted thereto.
- 16. (Currently Amended) The processing enclosure of claim 15, wherein the cantilevered mounted substrate support member comprises:
- a base member having a flange extending therefrom, the flange being configured to attach to an interior surface of the chamber body and form a smooth surface therewith;
- at least one cantilevered arm portion extending radially inward from the base member; and
- a substrate receiving member mounted to a distal end of the at least one cantilevered arm portion, the substrate receiving member having an annular outer surface.
- 17. (Previously Presented) The processing enclosure of claim 16, wherein the annular outer surface defines an annular passage between the outer surface and the annular interior processing region.

Page 2